Receipt date: 06/29/2006

1AP20 Rec'd PCT/7TO 29 JUN 2006

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			•	Application Number	New Application	
	TION DISC			Filing Date	Herewith	
SIAIEME	NT BY API	PLICA	N I	First Named Inventor	Fariba HATAMI et al	
				Group Art Unit	10584882 - GAU: 2815	
				Examiner Name	Jay C. Kim	
				Confirmation No.		
Sheet	1 of 4		Attorney Docket Number	3367-103		

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Examiner	Cite	U.S. Patent Document Number Kind Code ²		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document				
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¹Unique citation designation number. ²See attached Kinds of U.S. Patent Documents. ³Enter Office that issued the document, by the two-letter code. ⁴For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁴Applicant is to place a check mark here if English language translation is attached. AB indicates that only an English language abstract is attached.

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				Application Number	New Application 4882	
	TION DISC			Filing Date	Herewith	
SIAIEME	NT BY AP	PLICAI	N I	First Named Inventor	Fariba HATAMI et al	
				Group Art Unit	10584882 - GAU: 2815	
				Examiner Name	Jay C. Kim	
				Confirmation No.		
Sheet	2	of	4	Attorney Docket Number	3367-103	

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Examiner Signature			/Jay Kim/			Date Considered	03/11/2009	

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1AP20 Res'd PCT/TTO 29 JUN 2006

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STATEME	NI BY API	PLICAI	NI	First Named Inventor	Fariba HATAMI et al	
				Group Art Unit	10584882 - GAU: 2815	
				Examiner Name	Jay C. Kim	
				Confirmation No.		
Sheet	3	of 4		Attorney Docket Number	3367-103	

		NON PATENT LITERATURE DOCUMENTS	
Examiner Initials*	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T²
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Examiner

Signature

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		ATION DISC			Filing Date	Herewith		
51	AIEW	ENT BY API	PLICA	N I	First Named Inventor	Fariba HATAMI et al		
					Group Art Unit	10584882 - GAU: 2815		
					Examiner Name	Jay C. Kim		
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